Figure 1: Novel of ALD reactor.

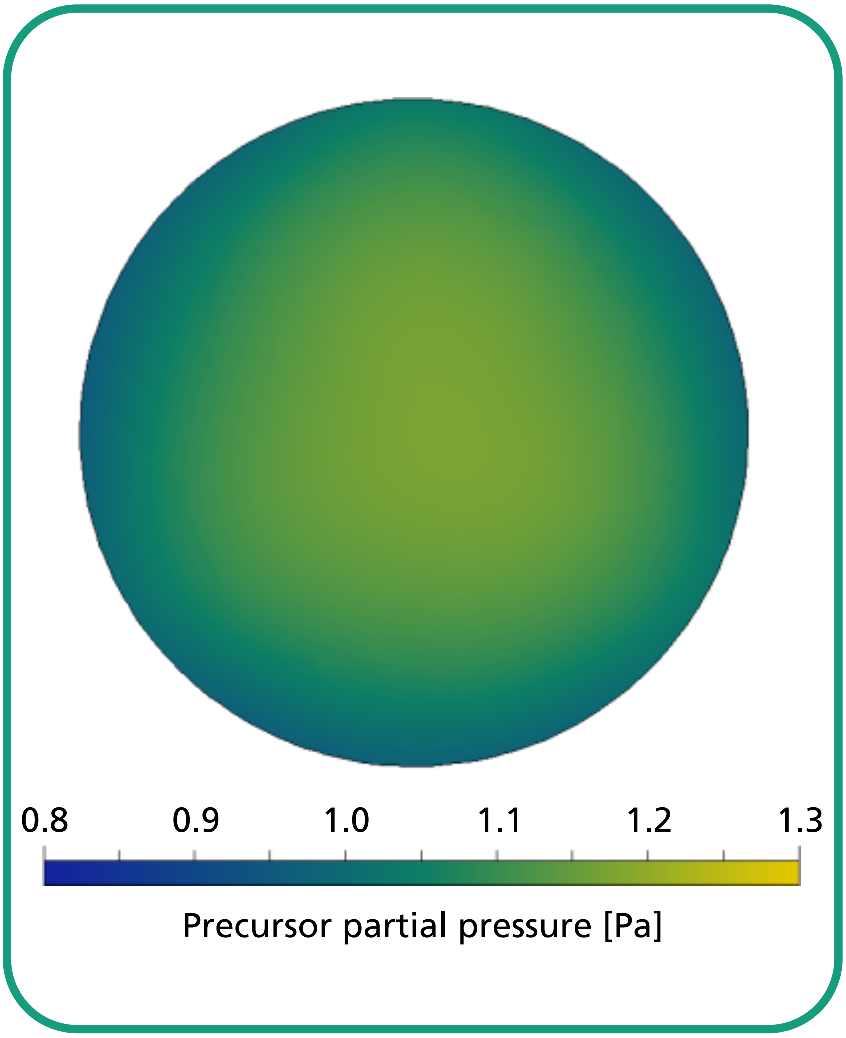

Figure 2: Simulation of precursor concentration on wafer surface.

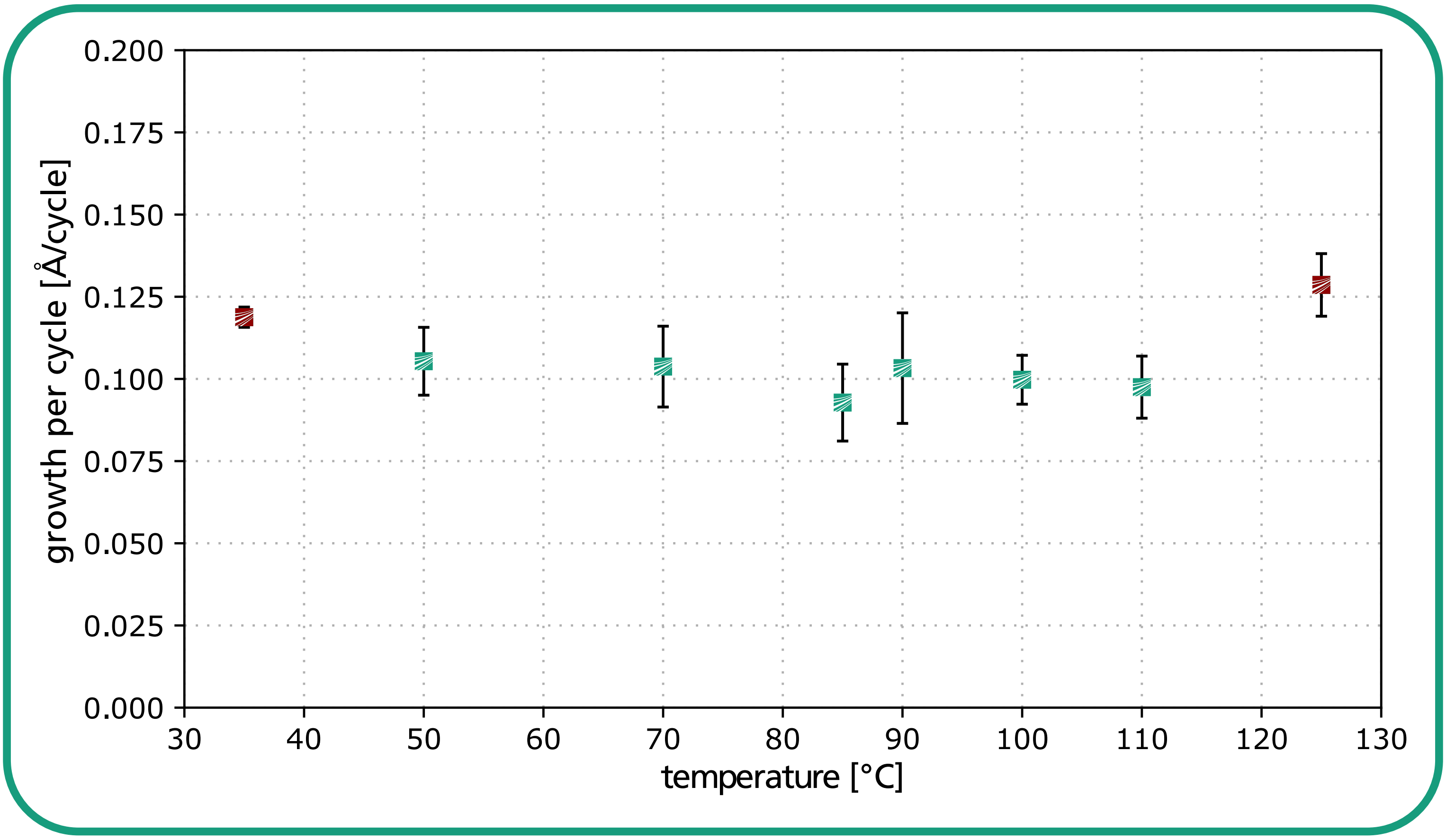

Figure 3: Temperature dependence of growth per cycle.